

# First Call for Papers

This leading annual workshop, now in its sixth year, focuses on the latest technical developments related to extreme ultraviolet (EUV) and soft X-ray sources. Papers on the generation of photons in this wavelength region using laser produced plasma (LPP), discharge produced plasma (DPP), EUV lasers, free electron lasers (FEL), synchrotrons and innovative concepts are invited. We welcome papers describing applications of these sources in EUV lithography for scanner and metrology applications, microscopy, and analytical instrumentation, and for supporting scientific research in material and biological sciences. Theoretical as well as experimental approaches will be accepted.

of 200 Abstracts words or fewer should be sent to abstracts@euvlitho.com by September 15, 2015. Please indicate whether an oral presentation or poster session is preferred, and include each author's full name, e-mail address, affiliation and mailing address. Please also include a brief biography and photograph for the presenting author, for inclusion in the abstract book.

This workshop will provide a forum for researchers in the EUV and soft X-ray areas to present their work and discuss a wide range of potential applications of these sources. Both researchers and endusers of EUV and soft X-ray sources will find this workshop valuable. Student papers are highly encouraged. The workshop proceedings will be published online and made available to all. Proceedings of the workshop are available online at our website, <u>www.euvlitho.com</u>. This workshop is co-organized by EUV Litho, Inc. and UCD. For sponsorship opportunities, please contact Dr. Padraig Dunne at <u>padraiq.dunne@ucd.ie</u>

#### Deadlines

#### Abstract Submission September 15, 2015

Author Notification September 21, 2015

## Abstract Submission

abstracts@euvlitho.com

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### **Registration** and **Travel** Info

www.euvlitho.com

